

Tres-Ark Liquid Dispense Module 2, 3 & 4

PRODUCT DESCRIPTION

FractalFill™ Blending Products are turn-key solutions for implementing real-time closed loop control and dispense of multi-variant chemical mixes to meet exacting requirements in advanced semiconductor wafer cleaning and etching processes. The Tres-Ark Liquid Dispense Module 2, 3 & 4, or TAK M2, TAK M3, and TAK M4, supply a single tool with two, three or four chemical mixes. A significant advantage with these models is the ability to control and prevent tool-to-tool chemical variability while providing Angstrom-level etch control.



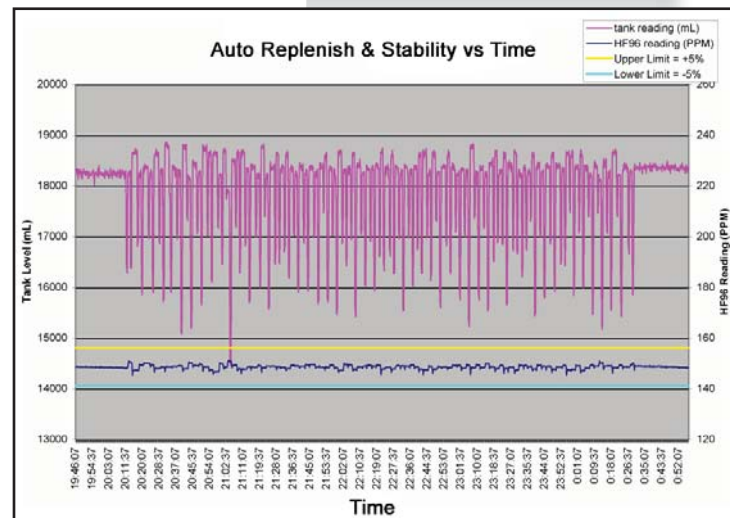
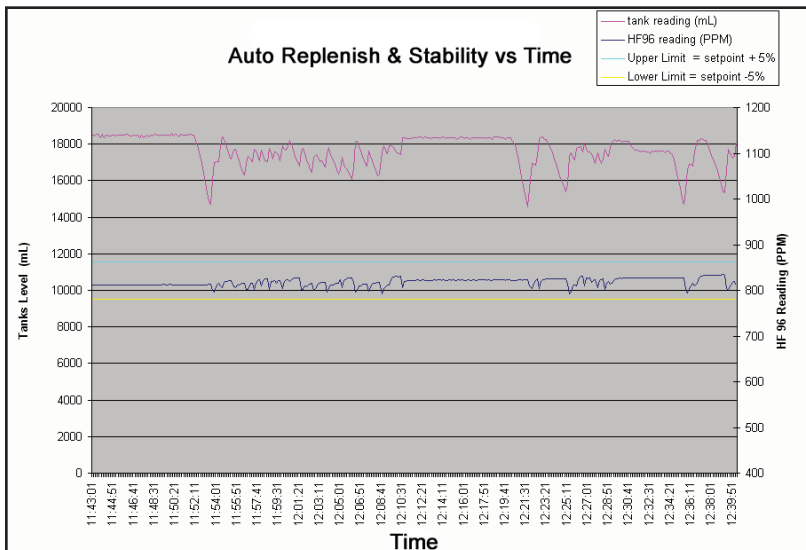
FACILITY REQUIREMENTS (M2, M3, M4)

- Power - 208 - 240 vac single phase (2, 4, 6 amp)
- CDA - (24, 36, 48 SCFM) at 100 psig
- N2 - 15 psi, 1/4" connection, 0.2 lpm
- DIW - 55 - 60 psi, 3/4", (20, 40, 60 lpm)
- Chemicals (2) - 30 - 60 psi: 1/4" connection, 1-3 lpm per module
- Exhaust - 100 scfm: 4" connection
- Drain - 3/4" connection, 15 gpm
- Sump Drain - 1/2" connection
- Delivery Flow Rate - (24, 36, 48 lpm)
- Pumps - (2, 3, 4 pumps)

Contact for customization questions

The chemical mix is always within the control limits even as demand levels fluctuate, as seen below

FRACTALFILL™ BLENDING DATA



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